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Editors: Arokia Nathan, Andrew Flewitt, Jack Hou, Seiichi Miyazaki and Jeffrey Yang

Index

[More information](#)

AUTHOR INDEX

- Adjallah, Y., 29
 Adriaenssens, Guy J., 211
 Al-Jassim, M.M., 87
 Anderson, Curtis, 29, 185
 Andreu, Jordi, 173
 Antonuk, L.E., 457
 Antony, Aldrin, 173
 Arai, Toshiaki, 243
 Asensi, José Miguel, 173
 Asomoza, Rene, 113
- Baiano, Alessandro, 483
 Ballif, Christophe, 265
 Banerjee, Arindam, 325
 Barata, Manuel, 225
 Becker, Christiane, 139
 Beenakker, Cees, 483
 Beglau, Dave, 325
 Behravan, M., 457
 Behrends, Jan, 139
 Bertomeu, Joan, 173
 Beyer, Wolfhard, 179
 Birkmire, R.W., 41
 Biswas, Rana, 331
 Blackwell, C., 29, 155
 Blomberg, Tom, 131
 Bobela, David C., 279
 Bowden, S., 41
 Branz, Howard M., 15, 259, 285
 Brinza, Monica, 211
 Brown, W.D., 345
 Brunner, Robert, 199
 Burrows, M.Z., 41
- Cabeça, R., 451
 Carius, Reinhard, 179, 293
 Carvalho, N., 407
 Chakraborty, Sudeshna, 279
 Chan, Kah-Yoong, 293
 Chang, Chung-Hsiang, 353, 443
 Chang, Jeff Hsin, 431, 463
 Checa, Nery D., 113
 Chen, Jian Z., 385
 Cheng, I-Chun, 385
 Cherenack, Kunigunde H., 471
- Choi, Joonhoo, 361
 Choi, Sung-Hwan, 361, 373
 Chou, Li-Jen, 353, 443
 Chu, Virginia, 339, 451
 Cohen, J. David, 149, 259, 325
 Collins, Robert W., 253
 Conde, Joao Pedro, 339, 451
 Cosme, Ismael, 419
- Das, U.K., 41
 Datta, Shouvik, 259
 DeMaggio, Greg, 325
 Derakhshandeh, Jaber, 483
 Devilee, Camile, 67
 De Wolf, Stefaan, 49
 Dickey, Elizabeth C., 253
 Diplo, P., 87
 Dogan, Pinar, 139
 Dorenkamper, Maarten, 67
 Drabold, D.A., 279
 Duggan, J.L., 217
 Dunand, Sylvain, 265
- El-Mohri, Y., 457
 Enomoto, Hirofumi, 315
 Escarré, Jordi, 173
 Esmaeili-Rad, Mohammad R., 379
- Fantoni, Alessandro, 225, 407
 Fenske, Frank, 139
 Fernandes, Miguel, 225, 407, 425
 Findikoglu, Alp T., 477
 Fujiwara, Hiroyuki, 21, 49, 437
- Gall, Stefan, 139
 Gaspar, Joao, 339
 Georgiev, Daniel, 393
 Gorka, Benjamin, 139
 Gorman, B., 217
 Gudovskikh, A.S., 75
 Guha, Subhendu, 61, 149, 273, 325
- Ha, Tae-Jun, 373
 Hailstone, Richard, 437
 Han, Min-Koo, 301, 361, 373

Cambridge University Press

978-1-107-40857-9 - Amorphous and Polycrystalline Thin-Film Silicon Science and Technology—2008: Materials Research Society Symposium Proceedings: Volume 1066

Editors: Arokia Nathan, Andrew Flewitt, Jack Hou, Seiichi Miyazaki and Jeffrey Yang

Index

[More information](#)

- Han, Sang-Myeon, 361
 Hänel, Tobias, 139
 Hata, Satoshi, 345
 Haukka, Suvi, 131
 Hayashi, Tsukasa, 167
 Hegedus, S.S., 41
 Heijna, Maurits C.R., 67
 Heiler, Gregory, 413, 425, 431, 463
 Hekmatshoar, Bahman, 471
 Hernandez, Salvador G., 113
 Hiroe, Akihiko, 307
 Holesinger, Terry G., 477
 Hollenstein, Christoph, 3
 Horn, Mark W., 253
 Hossain, K., 217
 Howling, Alan A., 3
 Hsieh, Chin-Hua, 353, 443
 Hugger, Peter G., 149, 325
- Imamura, Kentarou, 199
 Inagaki, Yoshio, 243
 Inayoshi, Yohei, 119
 Ishihara, Ryoichi, 483
 Ishikawa, Takamasa, 315
- Jergel, Matej, 199
 Jia, Haijun, 21
 Jiang, Chun-Sheng, 61, 87
 Jiao, Lihong (Heidi), 99
 Jiménez, Juan, 193
 Jones, Kim M., 285
 Ju, Tong, 35, 273
 Jurecka, Stanislav, 199
- Kakalios, J., 29, 155
 Kaki, Hirokazu, 167
 Kalinin, Valeri V., 399
 Kamoshita, Tomoyoshi, 315
 Kang, Dong-Won, 301
 Kao, Chyuan-Haur, 367
 Kattamis, Alex Z., 471
 Kawano, Shinichi, 315
 Kim, Kyung Ho, 431
 Kishore, Ram, 345
 Kiyofuji, Shinji, 315
 Kleider, J.P., 75
- Kling, Andreas, 193
 Knipp, Dietmar, 293
 Kobayashi, Hikaru, 199
 Kondo, Michio, 21, 49, 437
 Koniczek, M., 457
 Kopani, Martin, 199
 Kortshagen, Uwe, 29, 155, 185
 Kosarev, Andrey, 113, 419
 Kudriavtsev, Yurii, 113
 Kuk, Seung-Hee, 301
 Kuo, Yue, 231
 Kuraseko, Hiroshi, 21
 Kúš, Peter, 205
 Kuwano, Noriyuki, 345
 Kwong, Ian Chi Yan, 161
- Lai, Jackson, 413, 463
 Lavareda, G., 407
 Lee, Hyun Jung, 161
 Lee, Won-Kyu, 361, 373
 Leegwater, Hans, 67
 Lennartz, Dorothea, 179
 Li, J., 217
 Li, Jing, 253
 Li, Yang, 325
 Lin, Gong-Ru, 353, 443
 Lips, Klaus, 139
 Liu, Chi-Wee, 353
 Löffler, Jochen, 67
 Louro, Paula, 225, 407
 Luxembourg, Stefan L., 205
- Mariotti, Davide, 437
 Martin, Ina T., 285
 Martínez, Óscar, 193
 Matero, Raija, 131
 Matsumoto, Mitsutaka, 119
 McDaniel, F.D., 217
 McDonald, J., 457
 Mikula, Milan, 199
 Miyagi, Masahide, 315
 Moening, Joe, 393
 Morana, Bruno, 193
 Moreno, Mario M., 419
 Morosawa, Narihiro, 243
 Moutinho, H.R., 87

Cambridge University Press

978-1-107-40857-9 - Amorphous and Polycrystalline Thin-Film Silicon Science and Technology—2008: Materials Research Society Symposium Proceedings: Volume 1066

Editors: Arokia Nathan, Andrew Flewitt, Jack Hou, Seiichi Miyazaki and Jeffrey Yang

Index

[More information](#)

- Muñoz, Delfina, 173
Myasnikov, Alexandre M., 399
- Nakajima, Setsuo, 119
Nakamura, Tetsuro, 315
Naseem, Hameed, 345
Nathan, Arokia, 379, 413, 425, 431, 463
Neogi, A., 217
Niessen, Lars, 179
Nishihara, Hironori, 315
Nominanda, Helinda, 231
- Ogata, Kiyoshi, 167
Ohmi, Tadahiro, 307
Opila, R.L., 41
- Park, Joong-Hyun, 301
Park, Sang-Geun, 301, 361, 373
Paul, Oliver, 339
Pennartz, Frank, 179
Pi, Xiaodong, 155
Pieters, Bart Elger, 93
Pimentel, A.C., 451
Pincik, Emil, 199
Podraza, Nikolas J., 253
Poudel, P.R., 217
Prazeres, D.M.F., 451
- Rath, Jatindra K., 211
Rech, Bernd, 139
Reedy, Robert C., 285
Rodrigues, M., 451
Rodríguez, Andrés, 193
Rodríguez, Tomás, 193
Rojas, Fredy, 173
Romero, Manuel J., 87, 285
Root, Andrew, 131
Rout, B., 217
Ruske, Florian, 139
- Saito, Junichiro, 315
Sakakibara, Yasushi, 315
Sameshima, Toshiyuki, 107
Sangrador, Jesús, 193
Sazonov, Andrei, 161, 379, 463
- Schicho, Sandra, 93
Schropp, Ruud E.I., 211
Sharma, Renu, 345
Shimosawa, Makoto, 315
Shin, Kyung-Wook, 379
Soppe, Wim J., 67
Stella, Marco, 173
Stiebig, Helmut, 93, 293
Stradins, Paul, 15, 35, 285
Strahm, Benjamin, 3
Striakhilev, Denis, 413, 431, 463
Sturm, James C., 471
Su, Tining, 273
Suemitsu, Maki, 119
Sung, W.H., 367
Svreck, Vladimir, 437
- Tajari Mofrad, Mohammad Reza, 483
Takahashi, Eiji, 167
Takahashi, Masao, 199
Takano, Akihiro, 315
Tatsuki, Koichi, 243
Taylor, P. Craig, 35, 273, 279
Teplin, Charles W., 15, 61, 285
Teramoto, Akinobu, 307
Tian, Longzhang, 125
Tichelaar, Frans D., 205
To, B., 87
Tomokiyo, Yoshitsuga, 345
Tomyo, Atsushi, 167
Torchynska, Tatyana V., 145
Torres, Alfonso J., 113, 419
Toyoshima, Yasutake, 119
Tredwell, Timothy, 413, 425, 431, 463
- Uehara, Tsuyoshi, 119
Ugurlu, Ozan, 477
Urabe, Tetsuo, 243
Urabe, Yuji, 107
Uraoka, Yukiharu, 167
- Van Aken, Bas B., 67
van der Cingel, Johan, 483
Vieira, M., 407

Cambridge University Press

978-1-107-40857-9 - Amorphous and Polycrystalline Thin-Film Silicon Science and Technology—2008: Materials Research Society Symposium Proceedings: Volume 1066

Editors: Arokia Nathan, Andrew Flewitt, Jack Hou, Seiichi Miyazaki and Jeffrey Yang

Index

[More information](#)

- | | |
|---------------------------------------|----------------------------------|
| Vieira, Manuel Augusto, 225 | Yan, Baojie, 61, 149, 273, 325 |
| Vieira, Manuela, 225, 425 | Yan, Yanfa, 61 |
| Villar, Fernando, 173 | Yang, Jeffrey, 61, 149, 273, 325 |
| Vygranenko, Yuriy, 413, 425, 431, 463 | Young, David, 285 |
| | Yue, Guozhen, 61, 149, 325 |
| Wagner, Sigurd, 471 | Zeman, Miro, 205 |
| Wang, Xinwei, 125 | Zhao, Q., 457 |
| Wronski, Christopher R., 99, 253 | Zhou, Dayu, 331 |
| Wyrsh, Nicolas, 265 | Zyryanov, Vladislav E., 399 |
| | |
| Xu, Xixiang, 149, 325 | |
| Xu, Yueqin, 259 | |

SUBJECT INDEX

- amorphous, 29, 49, 75, 99, 113,
125, 145, 155, 259, 279,
315, 325, 345, 367, 385,
399, 413, 419, 451
- annealing, 21, 41, 217
- Ar, 217
- atomic layer deposition, 131
- barrier layer, 217
- biomedical, 413
- bonding, 279
- chemical vapor deposition (CVD)
(deposition), 173, 179, 193
- crystal growth, 167, 185, 399, 483
- crystalline, 3, 139, 243
- crystallographic structure, 21
- defects, 35, 99, 211, 259, 273
- devices, 161, 293, 373, 463
- display, 301
- elastic properties, 339
- electrical properties, 29, 75, 93,
367, 379, 419
- electron spin resonance, 35, 273
- electronic
material, 113
structure, 211
- energy generation, 265, 285
- epitaxy, 285, 477
- film, 353, 443
- Ge, 113
- grain boundaries, 87
- infrared (IR) spectroscopy, 131,
179, 205
- insulator, 107, 425
- ion-beam assisted deposition, 477
- laser
ablation, 437
annealing, 125, 243, 393, 483
- liquid, 107
- lithography (removal), 471
- luminescence, 145, 437
- memory, 231
- microelectro-mechanical
(MEMS), 339
- microelectronics, 161, 225, 265
- microstructure, 179, 393
- nanoscale, 437
- nanostructure, 15, 61, 145, 155,
193, 325
- nuclear magnetic resonance
(NMR), 279
- optical properties, 199, 253
- optoelectronic, 407, 425, 431, 451,
463
- oxide, 193
- passivation, 41, 107
- photoconductivity, 211, 225, 425
- photovoltaic, 49, 61, 67, 93, 149,
185, 205, 265, 325, 331
- plasma-enhanced CVD (PECVD)
(deposition), 3, 21, 61, 67, 119,
167, 253, 307, 315, 353,
367, 379, 385, 419, 443,
471
- polycrystal, 361, 457
- scanning probe microscopy
(SPM), 87
- semiconducting, 407
- sensor, 225, 407, 413, 431, 451
- Si, 3, 15, 29, 35, 41, 49, 75, 87, 99,
119, 125, 139, 149, 155,
161, 167, 173, 185, 231,
243, 253, 259, 285, 293,
301, 307, 315, 331, 345,
353, 361, 373, 385, 393,
399, 443, 477
- simulation, 331, 457
- surface reaction, 131

Cambridge University Press

978-1-107-40857-9 - Amorphous and Polycrystalline Thin-Film Silicon Science and Technology—2008: Materials Research Society Symposium Proceedings: Volume 1066

Editors: Arokia Nathan, Andrew Flewitt, Jack Hou, Seiichi Miyazaki and Jeffrey Yang

Index

[More information](#)

thin film, 15, 67, 93, 119, 139, 149,
173, 199, 231, 273, 293,
301, 307, 339, 361, 373,
379, 431, 457, 463, 471,
483

transmission electron microscopy
(TEM), 205, 345

x-ray reflectivity, 199